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(54) BASE MATERIAL FILM AND PHOTSENSITIVE PHOTOGRAPHIC MATERIAL USING THE SAME

(57)Abstract:

PURPOSE: To obtain a base material film having highly dimensional stability used suitably as a base material for a photographic film processing base material film, an original image film for printed wiring board, etc., and a photosensitive photographic material using the base material film.

CONSTITUTION: A SiO₂ layer is provided onto a plastic film by a vacuum thin film forming technique, and a thin film layer consisting of SiO_x (x meets 1.0<x<2.0) and fluorides of an alkaline earth metal is formed on its one side or both sides by the vacuum thin film forming technique.

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